Lithography optics

Jose Sasian OPTI 696A



Rules that rule optics

$$RES = k_1 \frac{\lambda}{NA}; \quad DOF = k_2 \frac{n\lambda}{NA^2}$$

k1~0.4-0.8 Raleigh resolution k1=0.61 K2~0.5 Wavelength=193nm

R(193 dry)=147nm (NA=0.8; k1=0.61)

DOF=151 nm

R(193 water)=110 nm

Must preserve imaging volume! Resolution and depth of focus are critical.

Wavelength/resolution/Year

λ	Resolution	Year
G-line 436 nm	512-1024 nm	1986
I-line 365 nm	256-512 nm	1992
KrF 248 nm	128-256 nm	1998
ArF 193 nm	64-128 nm	2004
Immersion	32-64 nm	2008
EUV 13.5 nm	8-32 nm	2016

Main optical parts of a micro-lithographic system

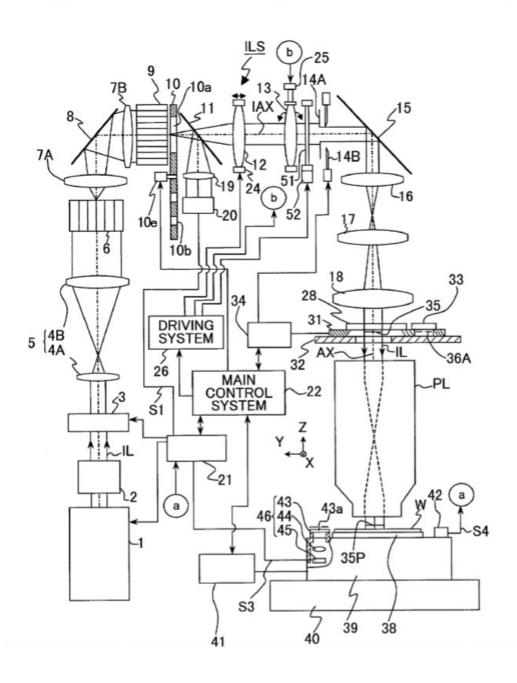
Light Source

Condenser

Mask/reticle

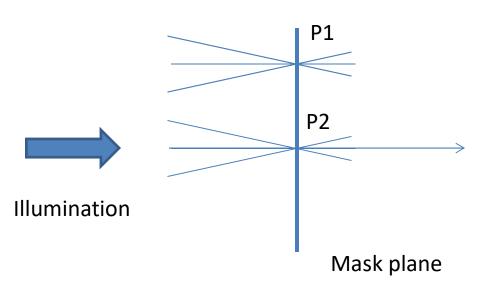
Projection Lens

Wafer



Illumination requirements

- Uniform illumination to ~1%.
- Every field point must be illuminated in the same way.



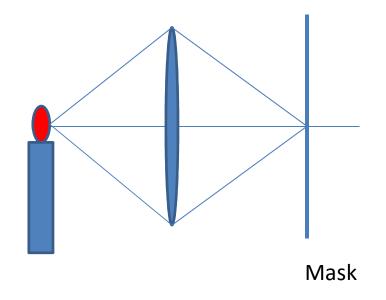
Angular ray spread is a metric for the degree of coherence. Every field point must have the same angular spread

$$\gamma_{12} = \frac{1}{\sqrt{I_1 I_2}} \int_{\mathbb{V}} u_1 u_2 d\sigma,$$

$$\left|\gamma_{12}\right|\approx(1-k^2\sigma_{\Delta W}^{-2})^{1/2}$$

Critical illumination

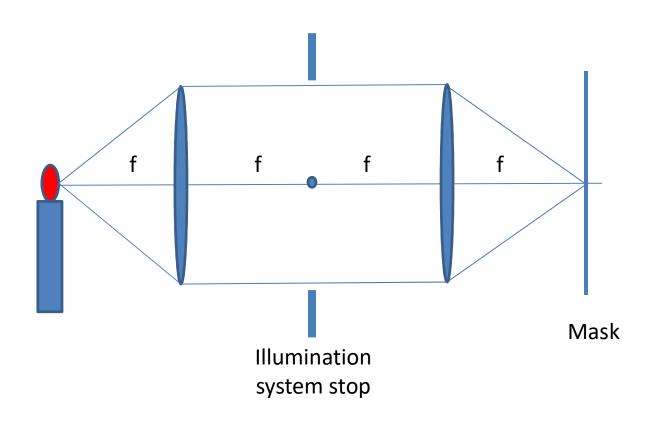
(From microscopy)



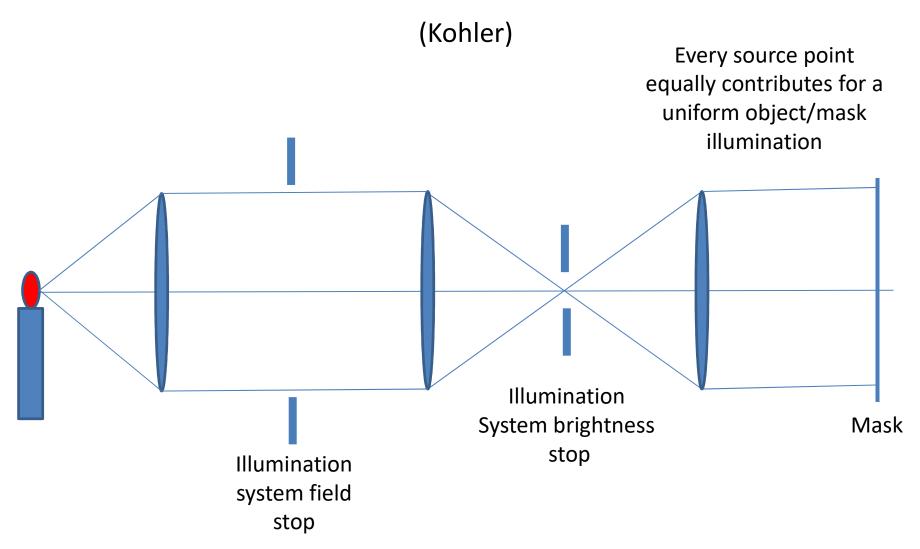
Source must be uniform to achieve Uniform object illumination

Critical illumination

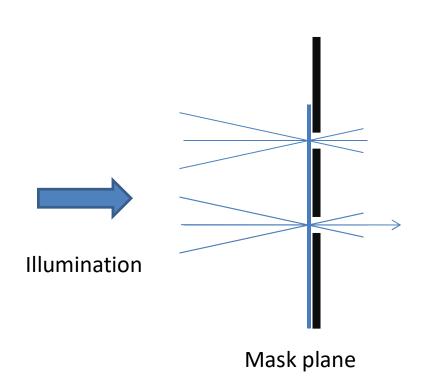
(4-f relay)



Uniform illumination

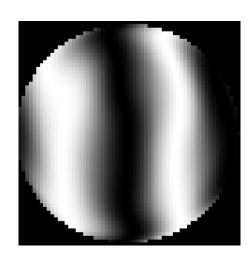


Young's double slit (pin-hole) experiment



The smaller the ray spread the more coherent the illumination would be as it will come more from a single source point.

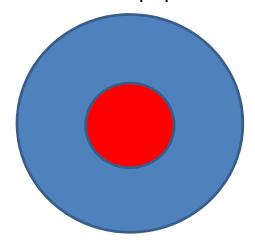
$$|\gamma_{12}| \approx (1 - k^2 \sigma_{\Lambda W}^2)^{1/2}$$



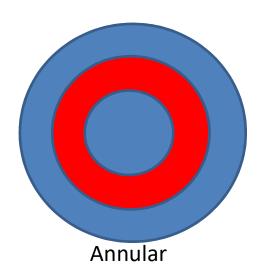
Fringe contrast will
Depend on degree
Of coherence between
the light from the two
Pin holes.

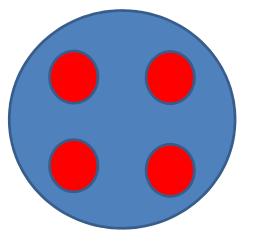
Illumination



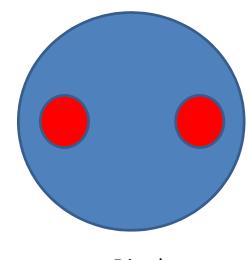


Sigma factor = d/D





Quadrupole



Dipole

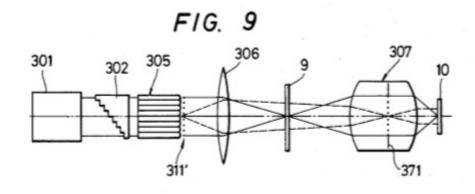
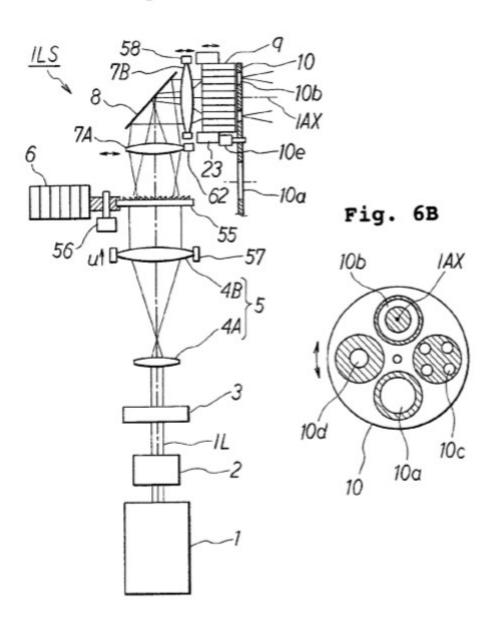
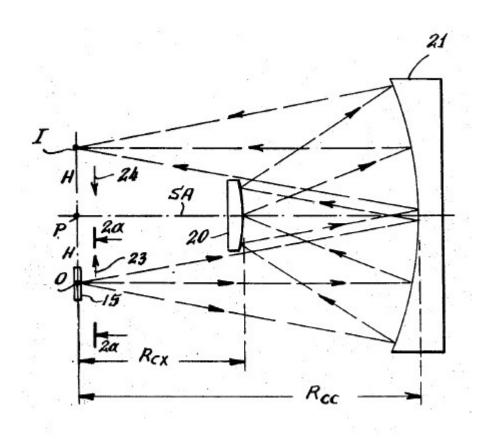


Fig. 6A



Projection lenses

Ring field system



[11] 3,748,015

[45] July 24, 1973

UNIT POWER IMAGING CATOPTRIC ANASTIGMAT

Inventor: Abe Offner, Darien, Conn.

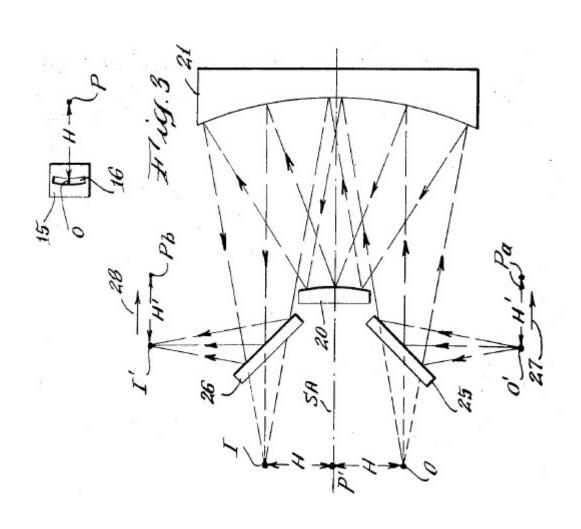
Assignee: The Perkin-Elmer Corporation,

Norwalk, Conn.

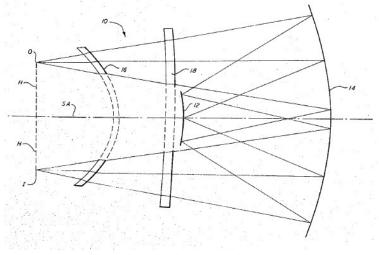
Filed: June 21, 1971

Doubly telecentric No primary aberrations

Unit power imaging catoptric anastigmatic



Restricted off-axis field system



RESTRICTED OFF-AXIS FIELD OPTICAL SYSTEM

Inventor: Abe Offner, Darien, Conn.

Assignee: The Perkin-Elmer Corporation,

Norwalk, Conn.

Appl. No.: 106,415

Filed: Dec. 21, 1979

4,293,186 5, 1981

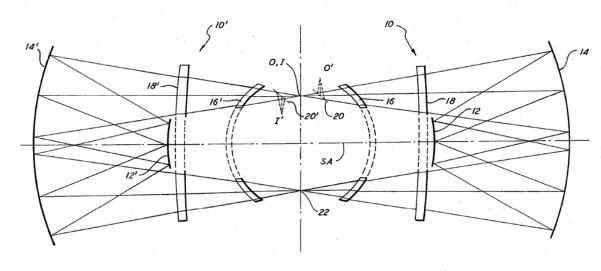
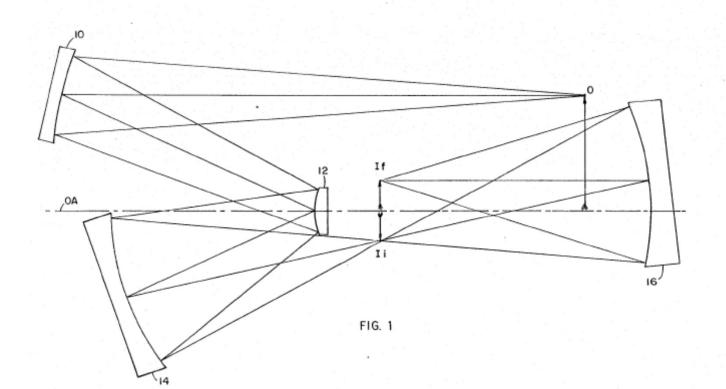
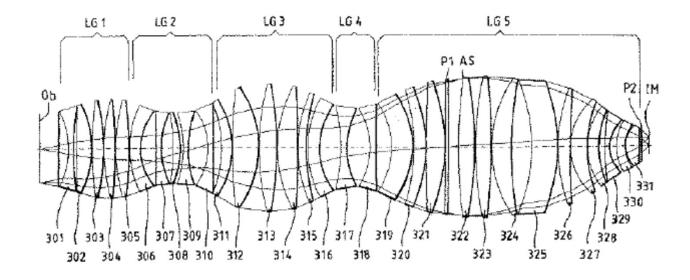


FIG. 2



Double-triple bulge full field



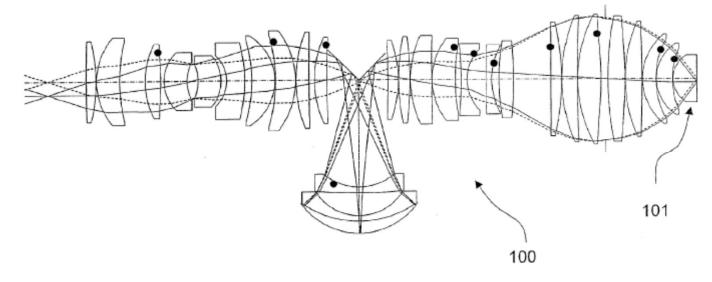


Fig. 5

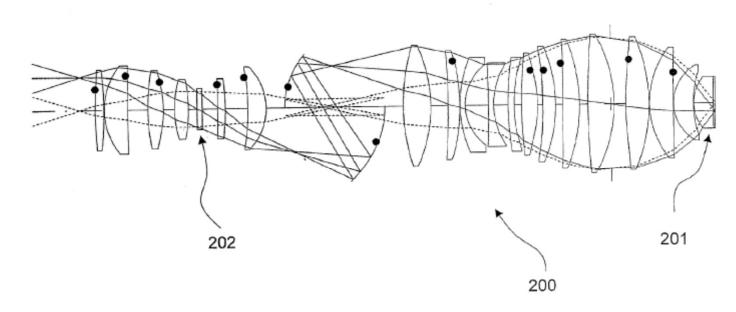
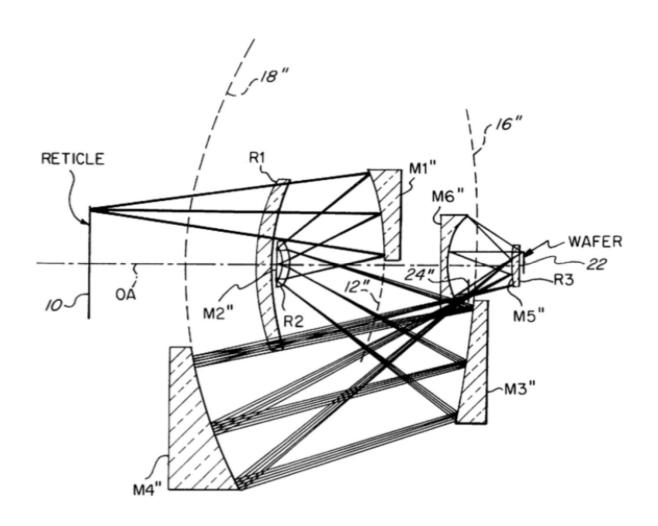
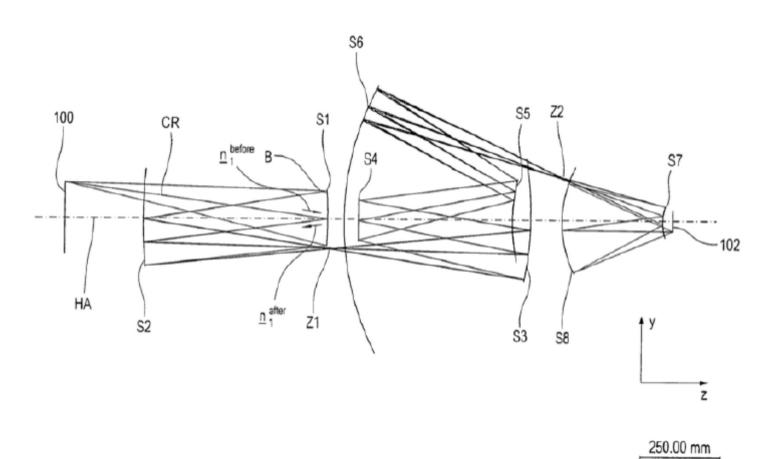


Fig. 6

U.S. Pat. No. 5,815,310 (1998)



U. S. Pat. No. 7,508,580 (2009)



Fly-eye integrators

OPTICAL COLLIMATING SYSTEM Filed Aug. 21, 1964

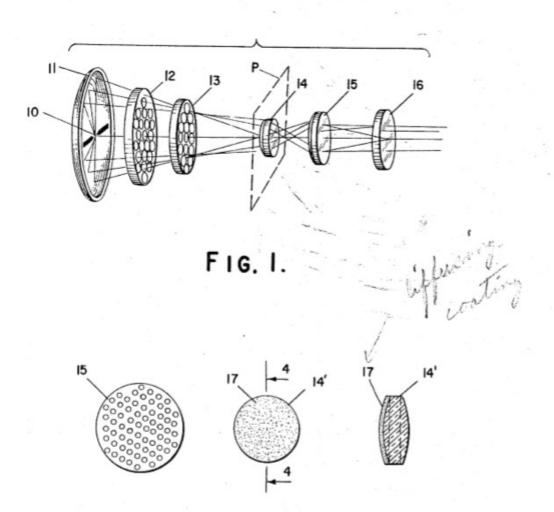
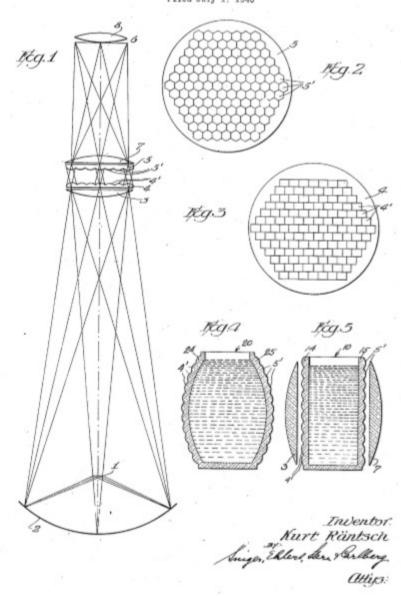


FIG. 2. FIG. 3. FIG. 4.

ILLUMINATING SYSTEM, PARTICULARLY FOR PROJECT. P PURPOSES Filed July 1, 1940



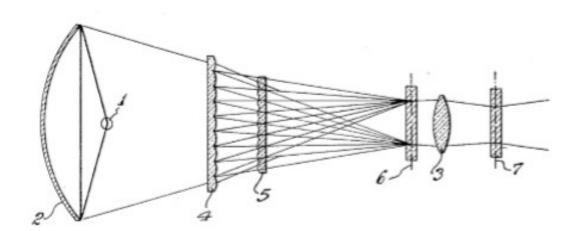
Aug. 20, 1957

H. ULFFERS

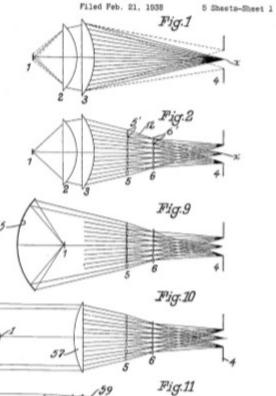
2,803,163

ILLUMINATING SYSTEM FOR PICTURE PROJECTORS

Filed May 18, 1953



ILLUMINATING SYSTEM



Jan. 9, 1940.

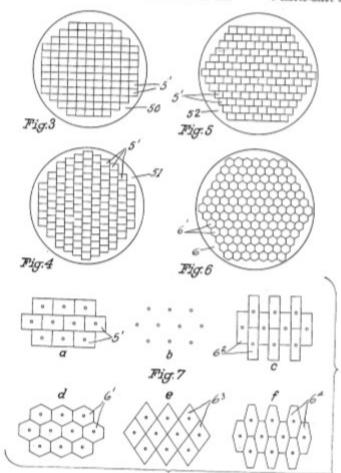
K. RÄNTSCH ET AL

ILLUMINATING SYSTEM

Filed Feb. 21, 1938

5 Sheets-Sheet 2

2,186,123



Rod integrators

US 2004/0071434 A

Fig.1

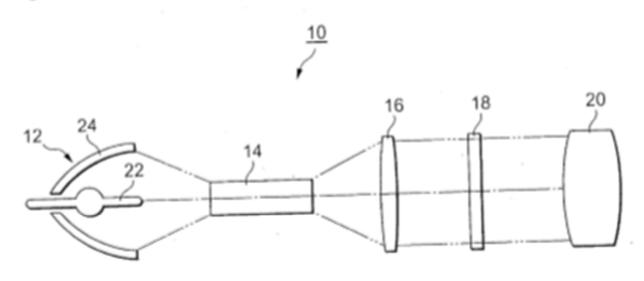
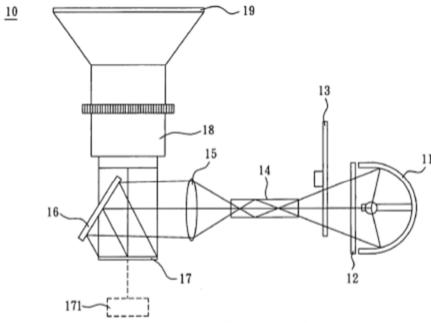


FIG. 1A (PRIOR ART)

US 7,850,315 B2



PRIOR ART FIG. 1

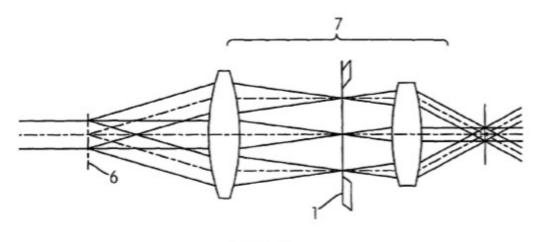
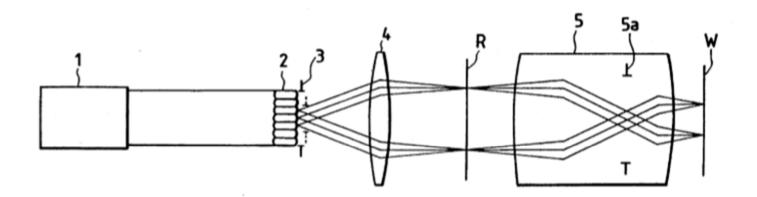


FIG. 1a

FIG. 3



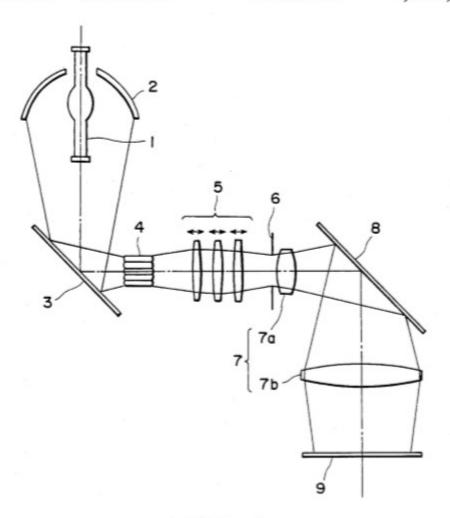


FIG. I

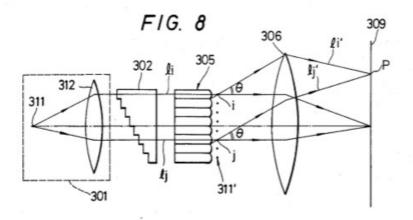
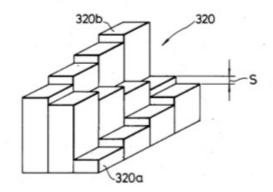
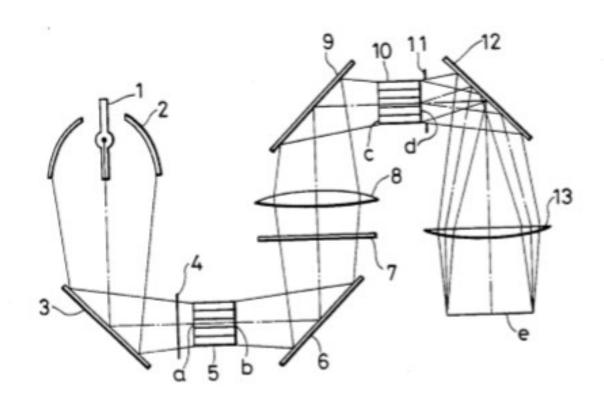


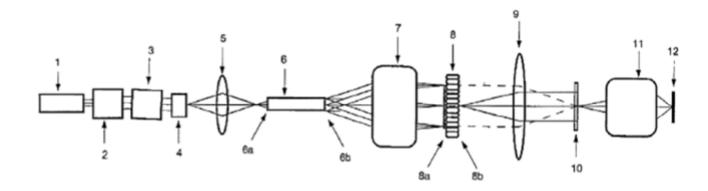
FIG. 9

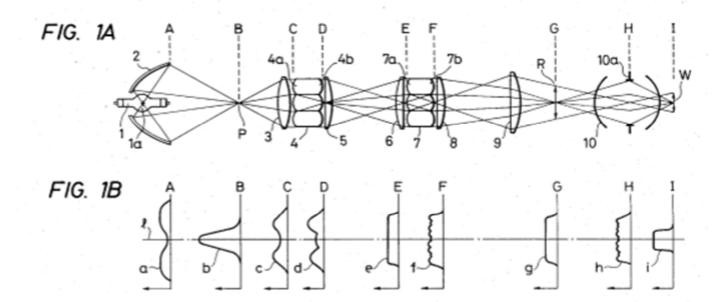
F/G. 10





Rod and fly-eye integrators





D. E. PRITCHARD

OPTICAL TUNNEL SYSTEM

Filed May 9, 1962

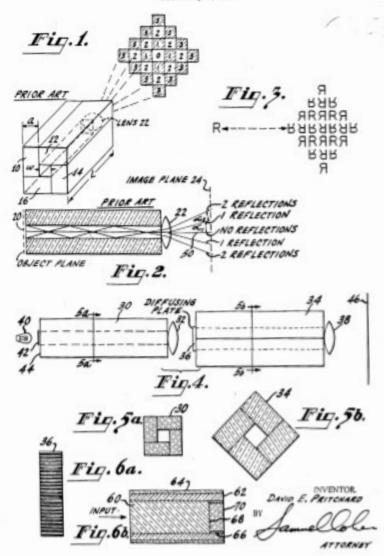
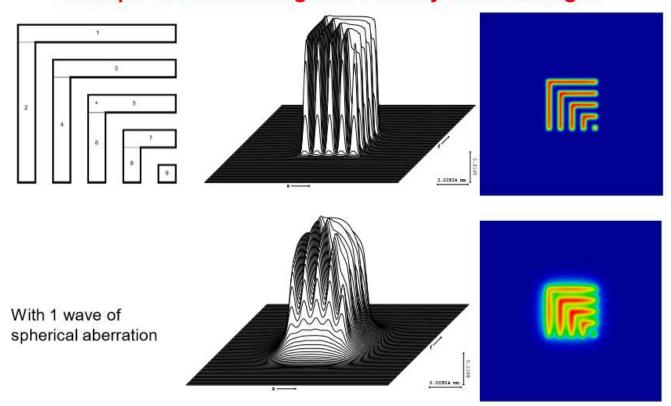


Image simulation

H. H. Hopkins equation

$$I(x,y) = \left(\frac{1}{f\lambda}\right)^2 \iint_{\infty} \sigma(x_0,y_0) |s(x,y)t(x,y)|^2 dx_0 dy_0$$

Example of Elbows Imaged in Partially Coherent Light



Effect of partial coherence on imaging an edge

